

SURFACE TREATMENT OF A DRY-DEVELOPED HARD MASK AND SURFACE TREATMENT COMPOSITIONS USED THEREFOR

ABSTRACT OF THE DISCLOSURE

- 5 A surface treatment process includes rinsing a substrate after a dry development process to remove residual resist material prior to patterning a hard mask layer. An amorphous carbon hard mask is dry developed and thereafter, the surface treatment includes an aqueous ammonium hydroxide and hydrogen peroxide composition. While the composition acts as a solvent to the resist, the composition
10 is selective to the amorphous carbon hard mask and the surface under the hard mask.

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